

US006911351B2

(12) United States Patent

Kidoguchi et al.

(10) Patent No.: US 6,911,351 B2

(45) **Date of Patent: Jun. 28, 2005**

(54) METHOD OF FABRICATING NITRIDE SEMICONDUCTOR, METHOD OF FABRICATING NITRIDE SEMICONDUCTOR DEVICE, NITRIDE SEMICONDUCTOR DEVICE, SEMICONDUCTOR LIGHT EMITTING DEVICE AND METHOD OF FABRICATING THE SAME

(75) Inventors: Isao Kidoguchi, Hyogo (JP); Akihiko Ishibashi, Osaka (JP); Ryoko Miyanaga, Nara (JP); Gaku Sugahara, Nara (JP); Masakatsu Suzuki, Osaka (JP); Masahiro Kume, Shiga (JP); Yuzaburo Ban, Osaka (JP); Kiyoyuki Morita, Kyoto (JP); Ayumu Tsujimura, Osaka (JP); Yoshiaki

Hasegawa, Osaka (JP)

(73) Assignee: Matsushita Electric Industrial Co.,

Ltd., Osaka (JP)

(*) Notice: Subject to any disclaimer, the term of this

patent is extended or adjusted under 35 U.S.C. 154(b) by 90 days.

(21) Appl. No.: 10/345,377

(22) Filed: Jan. 16, 2003

(65) Prior Publication Data

US 2003/0143771 A1 Jul. 31, 2003

Related U.S. Application Data

(62) Division of application No. 09/712,127, filed on Nov. 15, 2000.

(30) Foreign Application Priority Data

Nov. 15, 1999	(JP)	11-324010
Dec. 24, 1999	(JP)	11-367169
Dec. 27, 1999	(JP)	
Jan. 27, 2000	(JP)	
Feb. 3, 2000	(JP)	
Feb. 25, 2000	(JP)	
Apr. 21, 2000	(JP)	
Apr. 21, 2000	(JP)	

(51)	Int. Cl.	H01L 21/00
(52)	HS CL	128/16, 129/11, 129/17.

(52) **U.S. Cl.** **438/46**; 438/44; 438/4/; 438/604; 257/103

(56) References Cited

U.S. PATENT DOCUMENTS

 4,840,922 A
 6/1989 Kobayashi et al.

 4,855,256 A
 8/1989 Kobayashi et al.

 5,549,747 A
 * 8/1996 Bozler et al.

 117/43

(Continued)

FOREIGN PATENT DOCUMENTS

JP 60161489 1/1984

(Continued)

OTHER PUBLICATIONS

Tsvetanka et al., "Pendeo-Epitaxy: A new Approach for Lateral growth of Gallium Nitride Films", Journal of Electronic Materials, vol. 28, No. 4., L5–L8, Apr. 1999.

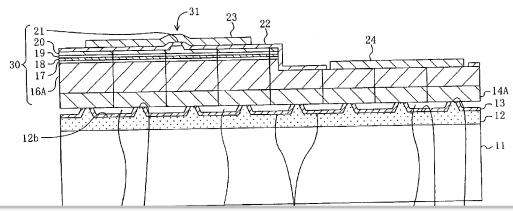
(Continued)

Primary Examiner—Amir Zarabian
Assistant Examiner—Khanh Duong
(74) Attorney, Agent, or Firm—McDermott Will & Emery
LLP

(57) ABSTRACT

The method of fabricating a nitride semiconductor of this invention includes the steps of forming, on a substrate, a first nitride semiconductor layer of $Al_uGa_vIn_wN$, wherein $0 \le u, v, w \le 1$ and u+v+w=1; forming, in an upper portion of the first nitride semiconductor layer, plural convexes extending at intervals along a substrate surface direction; forming a mask film for covering bottoms of recesses formed between the convexes adjacent to each other; and growing, on the first nitride semiconductor layer, a second nitride semiconductor layer of $Al_vGa_vIn_zN$, wherein $0 \le x$, $y, z \le 1$ and x+y+z=1, by using, as a seed crystal, C planes corresponding to top faces of the convexes exposed from the mask film.

87 Claims, 43 Drawing Sheets





U.S. PATENT DOCUMENTS

5,625,637	Α		4/1997	Mori et al.
5,739,554	Α		4/1998	Edmond et al.
5,972,730	Α		10/1999	Saito et al.
6,046,465	Α		4/2000	Wang et al.
6,153,010	Α	*	11/2000	Kiyoku et al 117/95
6,252,894	B1		6/2001	Sasanuma et al.
6,335,546	B 1		1/2002	Tsuda et al.
6,448,102	B1		9/2002	Kneissl et al.
6,608,327	B 1	*	8/2003	Davis et al 257/76
6,764,932	B2	*	7/2004	Kong et al 439/589
2001/0010372	A1		8/2001	Takeuchi et al.
2001/0026658	A1		10/2001	Althaus et al

FOREIGN PATENT DOCUMENTS

JP	62282474 A	5/1986
JP	02214182 A	2/1989
JP	11068256 A	8/1997
JP	11251631	9/1999
JP	11312825	11/1999

JP	2002-518826	12/1999
JP	2000-106455	4/2000

OTHER PUBLICATIONS

I. Kim et al., "Crystal tilting in GaN grown by pendeopitaxy method on sapphire substrate", Applied Physics Letters, vol. 75, No. 26, pp. 4109–4111, Dec. 27, 1999.

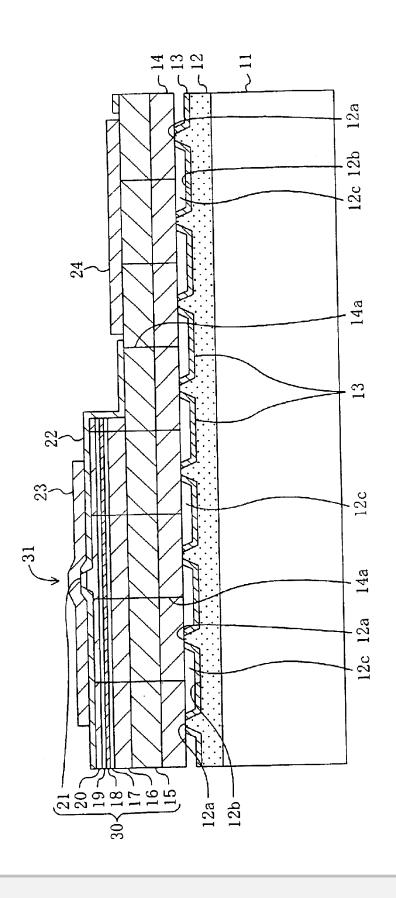
A. Sakai, "Transmission electron microscopy of defects in GaN films formed by epitaxial lateral overgrowth", Applied Physics Letters, vol. 73, No. 4, pp. 481–483, Jul. 27, 1998. H. Sone et al., "Optical and Crystalline Properties of Epitaxial–Lateral–Overgrown–GaN Using Tungsten Mask by Hydride Vapor Phase Epitaxy", Jpn. J. Appl. Phys. vol. 38 (1999), Part 2, No. 4A, pp. L356–L359, Apr. 1, 1999.

Tsvetanka et al., "Pendeo-Epitaxy: A new Approach for Lateral growth of Gallium Nitride Films", Journal of Electronic Materials, vol. 28, No. 4., L5–L8, Apr. 1999.

* cited by examiner



FIG. 1



Jun. 28, 2005

FIG. 2(a)

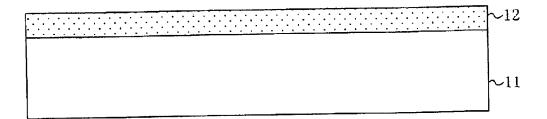


FIG. 2(b)

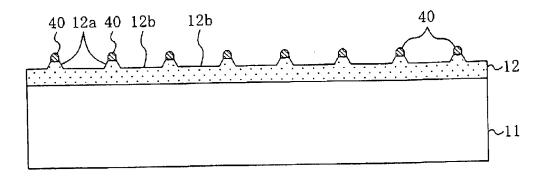




FIG. 3(a)

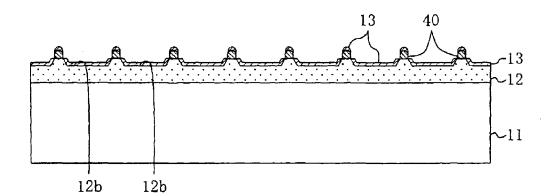
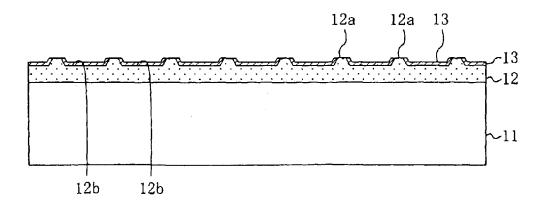


FIG. 3(b)





DOCKET

Explore Litigation Insights



Docket Alarm provides insights to develop a more informed litigation strategy and the peace of mind of knowing you're on top of things.

Real-Time Litigation Alerts



Keep your litigation team up-to-date with **real-time** alerts and advanced team management tools built for the enterprise, all while greatly reducing PACER spend.

Our comprehensive service means we can handle Federal, State, and Administrative courts across the country.

Advanced Docket Research



With over 230 million records, Docket Alarm's cloud-native docket research platform finds what other services can't. Coverage includes Federal, State, plus PTAB, TTAB, ITC and NLRB decisions, all in one place.

Identify arguments that have been successful in the past with full text, pinpoint searching. Link to case law cited within any court document via Fastcase.

Analytics At Your Fingertips



Learn what happened the last time a particular judge, opposing counsel or company faced cases similar to yours.

Advanced out-of-the-box PTAB and TTAB analytics are always at your fingertips.

API

Docket Alarm offers a powerful API (application programming interface) to developers that want to integrate case filings into their apps.

LAW FIRMS

Build custom dashboards for your attorneys and clients with live data direct from the court.

Automate many repetitive legal tasks like conflict checks, document management, and marketing.

FINANCIAL INSTITUTIONS

Litigation and bankruptcy checks for companies and debtors.

E-DISCOVERY AND LEGAL VENDORS

Sync your system to PACER to automate legal marketing.

